

Notice of Allowability	Application No.	Applicant(s)	
	10/676,877	NODA, TAIJI	
	Examiner Michael Trinh	Art Unit 2822	

-- **The MAILING DATE of this communication appears on the cover sheet with the correspondence address--**

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. This communication is responsive to RCE & Amendment filed July 27, 2006.
2. The allowed claim(s) is/are 1-5,7-14 and 18-37.
3. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 - a) All b) Some* c) None of the:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

* Certified copies not received: _____.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.
THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.

4. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
5. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
 - (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
 - 1) hereto or 2) to Paper No./Mail Date _____.
 - (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date _____.

Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).
6. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

Attachment(s)

1. Notice of References Cited (PTO-892)
2. Notice of Draftsperson's Patent Drawing Review (PTO-948)
3. Information Disclosure Statements (PTO-1449 or PTO/SB/08),
Paper No./Mail Date _____
4. Examiner's Comment Regarding Requirement for Deposit
of Biological Material
5. Notice of Informal Patent Application (PTO-152)
6. Interview Summary (PTO-413),
Paper No./Mail Date _____.
7. Examiner's Amendment/Comment
8. Examiner's Statement of Reasons for Allowance
9. Other _____.

Michael Trinh
Primary Examiner

Art Unit: 2822

DETAILED ACTION

*** This office action is in response to Applicant's RCE and Amendment filed July 27, 2006.

Claims 1-5,7-14,18-37 are pending, in which claims 19-37 have been newly added.

Allowable Subject Matter

1. Claims 1-5,7-14,18-37 are allowed.
2. The following is a statement of reasons for the indication of allowable subject matter:

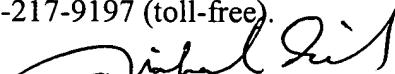
As already of record, Applicant's amendments and convincing remarks of record have overcome the rejections in the last office action. The references of record including Lee (2001/0041432), Sundaresan (6,190,179), Sonoda (6,696,341), etc., alone or in combination, do not fairly anticipatively disclose each and every aspect of the claimed method, or fairly make a *prima facie* obvious case of the claimed method as recited in base claim 1, the inclusion of a first step of implanting indium ions into the semiconductor substrate to form a dopant implantation layer in the channel formation region; a second step of implanting second dopant ions to form a first amorphous layer; after the first and second steps, performing a first thermal treatment to diffuse the first dopant ions from the dopant implantation layer, thereby forming a first diffused layer of the first conductivity type in the channel region; and after the third step, selectively forming a gate insulating film on the semiconductor substrate and a gate electrode thereon, wherein the first amorphous layer expands from the substrate surface to a region of the substrate deeper than the dopant implantation layer.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michael M. Trinh whose telephone number is (571) 272-1847. The examiner can normally be reached on M-F: 9:00 Am to 5:30 Pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Zandra Smith can be reached on (571) 272-2429. The central fax phone number is (703) 872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Oacs-16



Michael Trinh
Primary Examiner